Andre Anders

List of Publications by Year
in descending order

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415 papers	16,305 citations	16437 64 h-index	24232 110 g-index
427 all docs	427 docs citations	427 times ranked	7777 citing authors

#	Article	IF	Citations
1	Influence of the magnetic field on the discharge physics of a high power impulse magnetron sputtering discharge. Journal Physics D: Applied Physics, 2022, 55, 015202.	1.3	20
2	On the population density of the argon excited levels in a high power impulse magnetron sputtering discharge. Physics of Plasmas, 2022, 29, 023506.	0.7	1
3	High-quality transparent conductive indium oxide film deposition by reactive pulsed magnetron sputtering: Determining the limits of substrate heating. Applied Surface Science, 2022, 585, 152604.	3.1	6
4	10.1063/5.0088430.1. , 2022, , .		0
5	Building on excellence and reputation, a more inclusive Journal of Applied Physics evolves. Journal of Applied Physics, 2022, 131, .	1.1	0
6	Dynamics and 2D temperature distribution of plasma obtained by femtosecond laser-induced breakdown. Journal Physics D: Applied Physics, 2022, 55, 125204.	1.3	4
7	Properties of gallium oxide thin films grown by ion beam sputter deposition at room temperature. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	0.9	2
8	Foundations of physical vapor deposition with plasma assistance. Plasma Sources Science and Technology, 2022, 31, 083001.	1.3	27
9	Meeting todayâ€™s needs in applied physics publishing. Journal of Applied Physics, 2021, 129, .	1.1	1
10	On the electron energy distribution function in the high power impulse magnetron sputtering discharge. Plasma Sources Science and Technology, 2021, 30, 045011.	1.3	15
11	Role of Reaction Intermediate Diffusion on the Performance of Platinum Electrodes in Solid Acid Fuel Cells. Catalysts, 2021, 11, 1065.	1.6	3
12	Unravelling the ion-energy-dependent structure evolution and its implications for the elastic properties of (V,Al)N thin films. Acta Materialia, 2021, 214, 117003.	3.8	20
13	Cathode spot behavior in nitrogen and oxygen gaseous atmospheres and concomitant cathode surface modifications. Surface and Coatings Technology, 2021, 421, 127441.	2.2	8
14	High-resolution observation of cathode spots in a magnetically steered vacuum arc plasma source. Plasma Sources Science and Technology, 2021, 30, 095005.	1.3	10
15	Properties of secondary ions in ion beam sputtering of Ga2O3. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	0.9	4
16	On how to measure the probabilities of target atom ionization and target ion back-attraction in high-power impulse magnetron sputtering. Journal of Applied Physics, 2021, 129, .	1.1	17
17	Streak image observations of vacuum arc spots in a magnetically steered arc plasma source. , 2021, , .		0
18	High-resolution observation of cathodic arc spots in a magnetically steered arc plasma source in low pressure argon, nitrogen, and oxygen atmospheres. Journal of Applied Physics, 2021, 130, .	1.1	5

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19	Electron transport in high power impulse magnetron sputtering at low and high working gas pressure. Journal of Applied Physics, 2021, 130, .	1.1	4
20	Physics of high power impulse magnetron sputtering discharges. , 2020, , 265-332.		8
21	Erosion and cathodic arc plasma of Nbâ€"Al cathodes: composite versus intermetallic. Plasma Sources Science and Technology, 2020, 29, 025022.	1.3	10
22	Vanadium oxide coatings to self-regulate current sharing in high-temperature superconducting cables and magnets. Journal of Applied Physics, 2020, 128, .	1.1	8
23	Insights into surface modification and erosion of multi-element arc cathodes using a novel multilayer cathode design. Journal of Applied Physics, 2020, 127, .	1.1	13
24	Optimizing the deposition rate and ionized flux fraction by tuning the pulse length in high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2020, 29, 05LT01.	1.3	46
25	Serving a scientific community in an evolving research landscape. Journal of Applied Physics, 2020, 127, .	1.1	1
26	Properties of secondary particles for ion beam sputtering of silicon using low-energy oxygen ions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, 033011.	0.9	6
27	Ion beam sputtering of silicon: Energy distributions of sputtered and scattered ions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	15
28	Micro-propulsion based on vacuum arcs. Journal of Applied Physics, 2019, 125, .	1.1	38
29	Influence of Ar gas pressure on ion energy and charge state distributions in pulsed cathodic arc plasmas from Nbâ€"Al cathodes studied with high time resolution. Journal Physics D: Applied Physics, 2019, 52, 055201.	1.3	5
30	Plasma studies of a linear magnetron operating in the range from DC to HiPIMS. Journal of Applied Physics, 2018, 123, 043302.	1.1	21
31	Reduced atomic shadowing in HiPIMS: Role of the thermalized metal ions. Applied Surface Science, 2018, 433, 934-944.	3.1	27
32	Time and Energy-resolved Average Ion Charge States in Pulsed Cathodic Vacuum Arc Plasmas of Nb-A1 Cathodes as a Function of Ar Pressure. , 2018, , .		0
33	Time-resolved ion energy and charge state distributions in pulsed cathodic arc plasmas of Nbâ^'Al cathodes in high vacuum. Plasma Sources Science and Technology, 2018, 27, 055007.	1.3	10
34	Structural and Optical Studies of InGaN/GaN Superlattices Implanted with Eu Ions. MRS Advances, 2017, 2, 179-187.	0.5	0
35	Plasma potential of a moving ionization zone in DC magnetron sputtering. Journal of Applied Physics, 2017, 121, .	1.1	69
36	Sputtering of pure boron using a magnetron without a radio-frequency supply. Review of Scientific Instruments, 2017, 88, 043506.	0.6	16

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37	Tutorial: Reactive high power impulse magnetron sputtering (R-HiPIMS). Journal of Applied Physics, 2017, 121, .	1.1	275
38	Direct observation of spoke evolution in magnetron sputtering. Applied Physics Letters, 2017, 111, .	1.5	24
39	Phase tailoring of tantalum thin films deposited in deep oscillation magnetron sputtering mode. Surface and Coatings Technology, 2017, 314, 97-104.	2.2	27
40	All-solid-state tunable Bragg filters based on a phase transition material. , 2017, , .		0
41	Tunable Bragg filters with a phase transition material defect layer. Optics Express, 2016, 24, 20365.	1.7	19
42	Evidence for breathing modes in direct current, pulsed, and high power impulse magnetron sputtering plasmas. Applied Physics Letters, 2016, 108, .	1.5	21
43	Micropropulsion Based on Vacuum Arc Physics and Technology: A Review. , 2016, , .		2
44	Editorial: Celebrating the 85th Anniversary of Journal of Applied Physics. Journal of Applied Physics, 2016, 119, 010401.	1.1	0
45	Influence of ionisation zone motion in high power impulse magnetron sputtering on angular ion flux and NbO_xfilm growth. Plasma Sources Science and Technology, 2016, 25, 015022.	1.3	28
46	Temporal evolution of ion energy distribution functions and ion charge states of Cr and Cr-Al pulsed arc plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2015, 33, 061301.	0.9	6
47	Room Temperature Oxide Deposition Approach to Fully Transparent, Allâ€Oxide Thinâ€Film Transistors. Advanced Materials, 2015, 27, 6090-6095.	11.1	57
48	Editorial: Raising the barâ€"Providing a home. Journal of Applied Physics, 2015, 117, 010401.	1.1	1
49	Element- and charge-state-resolved ion energies in the cathodic arc plasma from composite AlCr cathodes in argon, nitrogen and oxygen atmospheres. Surface and Coatings Technology, 2015, 272, 309-321.	2.2	18
50	Adding high time resolution to charge-state-specific ion energy measurements for pulsed copper vacuum arc plasmas. Plasma Sources Science and Technology, 2015, 24, 045010.	1.3	15
51	Plasma of Vacuum Discharges: The Pursuit of Elevating Metal Ion Charge States, Including a Recent Record of Producing Bi¹³⁺. IEEE Transactions on Plasma Science, 2015, 43, 2310-2317.	0.6	16
52	Ion energies in high power impulse magnetron sputtering with and without localized ionization zones. Applied Physics Letters, 2015, 106, .	1.5	25
53	Localized heating of electrons in ionization zones: Going beyond the Penning-Thornton paradigm in magnetron sputtering. Applied Physics Letters, 2014, 105, 244104.	1.5	51
54	Propagation direction reversal of ionization zones in the transition between high and low current magnetron sputtering. Applied Physics Letters, 2014, 105, .	1.5	36

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55	Controlling ion fluxes during reactive sputter-deposition of SnO2:F. Journal of Applied Physics, 2014, 116, .	1.1	18
56	Editorial: Journal of Applied Physics in a changing world of scientific publication. Journal of Applied Physics, 2014, 116, 010401.	1.1	0
57	Fermi level stabilization and band edge energies in CdxZn1â^'xO alloys. Journal of Applied Physics, 2014, 115, .	1.1	37
58	Dyke Award - Ffor distinguished work on discharges and electrical insulation in vacuum. , 2014, , .		0
59	Ion energies in vacuum arcs: A critical review of data and theories leading to traveling potential humps. , 2014, , .		4
60	2-D mathematical modeling for a large electrochromic windowâ€"Part I. Solar Energy Materials and Solar Cells, 2014, 120, 1-8.	3.0	21
61	Smoothing of Discharge Inhomogeneities at High Currents in Gasless High Power Impulse Magnetron Sputtering. IEEE Transactions on Plasma Science, 2014, 42, 2856-2857.	0.6	10
62	Drifting Ionization Zone in DC Magnetron Sputtering Discharges at Very Low Currents. IEEE Transactions on Plasma Science, 2014, 42, 2578-2579.	0.6	19
63	Unusual Cathode Erosion Patterns Observed for Steered Arc Sources. IEEE Transactions on Plasma Science, 2014, 42, 2602-2603.	0.6	4
64	Asymmetric particle fluxes from drifting ionization zones in sputtering magnetrons. Plasma Sources Science and Technology, 2014, 23, 025007.	1.3	49
65	On the road to self-sputtering in high power impulse magnetron sputtering: particle balance and discharge characteristics. Plasma Sources Science and Technology, 2014, 23, 025017.	1.3	55
66	A review comparing cathodic arcs and high power impulse magnetron sputtering (HiPIMS). Surface and Coatings Technology, 2014, 257, 308-325.	2.2	200
67	Observation of multiple charge states and high ion energies in high-power impulse magnetron sputtering (HiPIMS) and burst HiPIMS using a LaB₆target. Plasma Sources Science and Technology, 2014, 23, 035001.	1.3	22
68	Spectroscopic imaging of self-organization in high power impulse magnetron sputtering plasmas. Applied Physics Letters, 2013, 103, .	1.5	51
69	On sheath energization and Ohmic heating in sputtering magnetrons. Plasma Sources Science and Technology, 2013, 22, 045005.	1.3	72
70	Size and composition-controlled fabrication of thermochromic metal oxide nanocrystals. Journal Physics D: Applied Physics, 2013, 46, 362001.	1.3	18
71	Drifting potential humps in ionization zones: The â€œpropeller bladesâ€•of high power impulse magnetron sputtering. Applied Physics Letters, 2013, 103, .	1.5	75
72	Transparent and conductive indium doped cadmium oxide thin films prepared by pulsed filtered cathodic arc deposition. Applied Surface Science, 2013, 265, 738-744.	3.1	55

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73	Structural, optical, and electrical properties of indium-doped cadmium oxide films prepared by pulsed filtered cathodic arc deposition. Journal of Materials Science, 2013, 48, 3789-3797.	1.7	28
74	Dopant-induced band filling and bandgap renormalization in CdOâ€‰:â€‰In films. Journal Physics D: Applied Physics, 2013, 46, 195102.	1.3	35
75	Estimating electron drift velocities in magnetron discharges. Vacuum, 2013, 89, 53-56.	1.6	18
76	Crystal structure and properties of CdxZn1âˆ’xO alloys across the full composition range. Applied Physics Letters, 2013, 102, .	1.5	60
77	Modeling of optical and energy performance of tungsten-oxide-based electrochromic windows including their intermediate states. Solar Energy Materials and Solar Cells, 2013, 108, 129-135.	3.0	32
78	Ion Charge State Distributions of Al and Cr in Cathodic Arc Plasmas From Composite Cathodes in Vacuum, Argon, Nitrogen, and Oxygen. IEEE Transactions on Plasma Science, 2013, 41, 1929-1937.	0.6	20
79	Drifting localization of ionization runaway: Unraveling the nature of anomalous transport in high power impulse magnetron sputtering. Journal of Applied Physics, 2012, 111, 053304.	1.1	143
80	Charge state distributions of Al and Cr cathodic arc plasmas. , 2012, , .		1
81	Improved structural and electrical properties of thin ZnO:Al films by dc filtered cathodic arc deposition. Journal of Materials Research, 2012, 27, 857-862.	1.2	4
82	Plasma flares in high power impulse magnetron sputtering. Applied Physics Letters, 2012, 101, .	1.5	45
83	Thermal decomposition and fractal properties of sputter-deposited platinum oxide thin films. Journal of Materials Research, 2012, 27, 829-836.	1.2	13
84	The â€˜recycling trapâ€™: a generalized explanation of discharge runaway in high-power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2012, 45, 012003.	1.3	85
85	Determining the nonparabolicity factor of the CdO conduction band using indium doping and the Drude theory. Journal Physics D: Applied Physics, 2012, 45, 425302.	1.3	42
86	The evolution of ion charge states in cathodic vacuum arc plasmas: a review. Plasma Sources Science and Technology, 2012, 21, 035014.	1.3	62
87	Phase transitions in vacuum arcs in the context of liquid metal arc sources. , 2012, , .		3
88	Self-organization and self-limitation in high power impulse magnetron sputtering. Applied Physics Letters, 2012, 100, .	1.5	73
89	Plasma potential mapping of high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2012, 111, .	1.1	75
90	Modelling of target effects in reactive HIPIMS. IOP Conference Series: Materials Science and Engineering, 2012, 39, 012008.	0.3	7

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91	Boron-rich plasma by high power impulse magnetron sputtering of lanthanum hexaboride. Journal of Applied Physics, 2012, 112, .	1.1	8
92	Efficient, Low Cost Synthesis of Sodium Platinum Bronze Na_xPt₃O₄. Chemistry of Materials, 2012, 24, 2429-2432.	3.2	6
93	Gas rarefaction and the time evolution of long high-power impulse magnetron sputtering pulses. Plasma Sources Science and Technology, 2012, 21, 045004.	1.3	82
94	Evaluation of species-specific score cutoff values of routinely isolated clinically relevant bacteria using a direct smear preparation for matrix-assisted laser desorption/ionization time-of-flight mass spectrometry-based bacterial identification. European Journal of Clinical Microbiology and Infectious Diseases, 2012, 31, 1109-1119.	1.3	33
95	Analysis of Bulk and Thin Film Model Samples Intended for Investigating the Strain Sensitivity of Niobium-Tin. IEEE Transactions on Applied Superconductivity, 2011, 21, 2550-2553.	1.1	6
96	Achieving high mobility ZnOâ€‰:â€‰Al at very high growth rates by dc filtered cathodic arc deposition. Journal Physics D: Applied Physics, 2011, 44, 232003.	1.3	34
97	A synchronized emissive probe for time-resolved plasma potential measurements of pulsed discharges. Review of Scientific Instruments, 2011, 82, 093505.	0.6	10
98	Dynamically Modulating the Surface Plasmon Resonance of Doped Semiconductor Nanocrystals. Nano Letters, 2011, 11, 4415-4420.	4.5	491
99	Measurements of the Ion Species of Cathodic Arc Plasma in an Axial Magnetic Field. IEEE Transactions on Plasma Science, 2011, 39, 1272-1276.	0.6	7
100	Dense Metal Plasma in a Solenoid for Ion Beam Neutralization. IEEE Transactions on Plasma Science, 2011, 39, 1386-1393.	0.6	11
101	Chemistry, phase formation, and catalytic activity of thin palladium-containing oxide films synthesized by plasma-assisted physical vapor deposition. Surface and Coatings Technology, 2011, 205, S171-S177.	2.2	33
102	Discharge physics of high power impulse magnetron sputtering. Surface and Coatings Technology, 2011, 205, S1-S9.	2.2	225
103	A Plasma Lens for Magnetron Sputtering. IEEE Transactions on Plasma Science, 2011, 39, 2528-2529.	0.6	18
104	Identification of Ternary Phases in TiBC/aâ€C Nanocomposite Thin Films: Influence on the Electrical and Optical Properties. Plasma Processes and Polymers, 2011, 8, 579-588.	1.6	10
105	Optical properties of ferromagnetic ytterbiumâ€doped IIIâ€nitride epilayers. Physica Status Solidi C: Current Topics in Solid State Physics, 2011, 8, 2185-2187.	0.8	4
106	Preparation of high transmittance ZnO:Al film by pulsed filtered cathodic arc technology and rapid thermal annealing. Applied Surface Science, 2011, 257, 7019-7022.	3.1	8
107	Hollow Plasma in a Solenoid. IEEE Transactions on Plasma Science, 2011, 39, 2888-2889.	0.6	1
108	High Rate Deposition of High Quality ZnO:Al by Filtered Cathodic Arc. Materials Research Society Symposia Proceedings, 2011, 1315, 1.	0.1	1

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109	Epitaxy of Ultrathin NiSi2 Films with Predetermined Thickness. Electrochemical and Solid-State Letters, 2011, 14, H268.	2.2	21
110	Optical studies of strained InGaN/GaN quantum structures implanted with europium for red light emitting diodes. , 2011, , .		0
111	High quality ZnO:Al transparent conducting oxide films synthesized by pulsed filtered cathodic arc deposition. Thin Solid Films, 2010, 518, 3313-3319.	0.8	48
112	A structure zone diagram including plasma-based deposition and ion etching. Thin Solid Films, 2010, 518, 4087-4090.	0.8	641
113	High power impulse magnetron sputtering and related discharges: Scalable plasma sources for plasma-based ion implantation and deposition. Surface and Coatings Technology, 2010, 204, 2864-2868.	2.2	51
114	Optical and magnetic properties of GaN epilayers implanted with ytterbium. Journal of Rare Earths, 2010, 28, 931-935.	2.5	10
115	A self-sputtering ion source: A new approach to quiescent metal ion beams. Review of Scientific Instruments, 2010, 81, 02B306.	0.6	10
116	Resonant Inelastic Scattering Spectra of Free Molecules with Vibrational Resolution. Physical Review Letters, 2010, 104, 193002.	2.9	126
117	Beneficial silver: antibacterial nanocomposite Ag-DLC coating to reduce osteolysis of orthopaedic implants. Journal of Physics: Conference Series, 2010, 252, 012005.	0.3	6
118	Ion acceleration and cooling in gasless self-sputtering. Applied Physics Letters, 2010, 97, .	1.5	21
119	On the deactivation of the dopant and electronic structure in reactively sputtered transparent Al-doped ZnO thin films. Journal Physics D: Applied Physics, 2010, 43, 132003.	1.3	34
120	Compression and strong rarefaction in high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2010, 108, .	1.1	73
121	Origin of the Delayed Current Onset in High-Power Impulse Magnetron Sputtering. IEEE Transactions on Plasma Science, 2010, 38, 3028-3034.	0.6	71
122	Deposition rates of high power impulse magnetron sputtering: Physics and economics. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2010, 28, 783-790.	0.9	172
123	Distance-dependent plasma composition and ion energy in high power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2010, 43, 275204.	1.3	23
124	Supersonic metal plasma impact on a surface: an optical investigation of the pre-surface region. Journal Physics D: Applied Physics, 2010, 43, 135201.	1.3	7
125	Antibacterial efficacy of advanced silver-amorphous carbon coatings deposited using the pulsed dual cathodic arc technique. Journal of Physics: Conference Series, 2010, 252, 012012.	0.3	17
126	Energetic deposition of metal ions: observation of self-sputtering and limited sticking for off-normal angles of incidence. Journal Physics D: Applied Physics, 2010, 43, 065206.	1.3	18

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127	Unfiltered and Filtered Cathodic Arc Deposition. , 2010, , 466-531.		14
128	Ion species and charge states of vacuum arc plasma with gas feed and longitudinal magnetic field. , 2010, , .		0
129	A seemingly simple task: Filling a solenoid volume in vacuum with dense plasma. , 2010, , .		0
130	Broad, intense, quiescent beam of singly charged metal ions obtained by extraction from self-sputtering plasma far above the runaway threshold. Journal of Applied Physics, 2009, 106, 023306.	1.1	12
131	Structural and spectroscopic studies of InGaN/GaN quantum structures implanted with rare earth ions. , 2009, , .		0
132	Physical limits for high ion charge states in pulsed discharges in vacuum. Journal of Applied Physics, 2009, 105, 043303.	1.1	16
133	A discussion on the absence of plasma in spark plasma sintering. Scripta Materialia, 2009, 60, 835-838.	2.6	204
134	Electronic structure and conductivity of nanocomposite metal (Au, Ag, Cu, Mo)-containing amorphous carbon films. Solid State Sciences, 2009, 11, 1742-1746.	1.5	32
135	Impact of Annealing on the Conductivity of Amorphous Carbon Films Incorporating Copper and Gold Nanoparticles Deposited by Pulsed Dual Cathodic Arc. Plasma Processes and Polymers, 2009, 6, S438.	1.6	9
136	A space-charge-neutralizing plasma for beam drift compression. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2009, 606, 22-30.	0.7	23
137	Progress in beam focusing and compression for warm-dense matter experiments. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2009, 606, 75-82.	0.7	45
138	Surface transformation of graphite or diamond following Highly Charged Ion irradiation. Nuclear Instruments & Methods in Physics Research B, 2009, 267, 678-682.	0.6	2
139	Electronic Structure of Water Molecules Confined in a Micelle Lattice. Journal of Physical Chemistry B, 2009, 113, 8201-8205.	1.2	20
140	Local Electronic Structure of Functional Groups in Glycine As Anion, Zwitterion, and Cation in Aqueous Solution. Journal of Physical Chemistry B, 2009, 113, 16002-16006.	1.2	38
141	Spectra and energy levels of Yb3+ in AlN. Journal of Applied Physics, 2009, 106, 013106.	1.1	24
142	Evolution of the plasma composition of a high power impulse magnetron sputtering system studied with a time-of-flight spectrometer. Journal of Applied Physics, 2009, 105, .	1.1	37
143	Self-Sputtering Far above the Runaway Threshold: An Extraordinary Metal-Ion Generator. Physical Review Letters, 2009, 102, 045003.	2.9	72
144	Plasma â€œanti-assistanceâ€•and â€œself-assistanceâ€•to high power impulse magnetron sputtering. Journal of Applied Physics, 2009, 105, .	1.1	38

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145	Simulations and experiments of intense ion beam current density compression in space and time. Physics of Plasmas, 2009, 16, 056701.	0.7	15
146	Deep oxidation of methane on particles derived from YSZ-supported Pdâ€"Pt-(O) coatings synthesized by Pulsed Filtered Cathodic Arc. Catalysis Communications, 2009, 10, 1410-1413.	1.6	9
147	Functionalization of hydrogen-free diamond-like carbon films using open-air dielectric barrier discharge atmospheric plasma treatments. Applied Surface Science, 2008, 254, 5323-5328.	3.1	16
148	Electrochromically switched, gas-reservoir metal hydride devices with application to energy-efficient windows. Thin Solid Films, 2008, 517, 1021-1026.	0.8	16
149	Physics of plasmaâ€based ion implantation & deposition (PBIID) and high power impulse magnetron sputtering (HIPIMS): A comparison. Physica Status Solidi (A) Applications and Materials Science, 2008, 205, 965-970.	0.8	8
150	Comparative surface and nano-tribological characteristics of nanocomposite diamond-like carbon thin films doped by silver. Applied Surface Science, 2008, 255, 2551-2556.	3.1	174
151	Structure and properties of silver-containing a-C(H) films deposited by plasma immersion ion implantation. Surface and Coatings Technology, 2008, 202, 3675-3682.	2.2	87
152	Coalescence of magnetron-sputtered silver islands affected by transition metal seeding (Ni, Cr, Nb, Zr,) Tj ETQq0 0 0 rgBT /Overlock 10 T	0.8	38
153	MeV-ion beam analysis of the interface between filtered cathodic arc-deposited a-carbon and single crystalline silicon. Nuclear Instruments & Methods in Physics Research B, 2008, 266, 5175-5179.	0.6	2
154	Macroparticles. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 265-298.	0.1	0
155	Reactive Deposition. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 409-428.	0.1	1
156	The absence of plasma in â€œspark plasma sinteringâ€. Journal of Applied Physics, 2008, 104, .	1.1	142
157	Film Deposition by Energetic Condensation. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 363-407.	0.1	8
158	The Physics of Cathode Processes. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 75-174.	0.1	7
159	Self-sputtering runaway in high power impulse magnetron sputtering: The role of secondary electrons and multiply charged metal ions. Applied Physics Letters, 2008, 92, .	1.5	84
160	Sputtering in vacuum: A technology for ultraclean metallization and space propulsion. , 2008, , .		1
161	Gasless sputtering: Opportunities for ultraclean metallization, coatings in space, and propulsion. Applied Physics Letters, 2008, 92, .	1.5	71
162	The electronic structure of tungsten oxide thin films prepared by pulsed cathodic arc deposition and plasma-assisted pulsed magnetron sputtering. Journal of Physics Condensed Matter, 2008, 20, 175216.	0.7	5

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163	Cathodic Arcs. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , .	0.1	443
164	Spatial distribution of average charge state and deposition rate in high power impulse magnetron sputtering of copper. Journal Physics D: Applied Physics, 2008, 41, 135210.	1.3	42
165	A Theoretical Analysis of Vacuum Arc Thruster and Vacuum Arc Ion Thruster Performance. IEEE Transactions on Plasma Science, 2008, 36, 2167-2179.	0.6	76
166	Electrical properties of a-C: Mo films produced by dual-cathode filtered cathodic arc plasma deposition. Diamond and Related Materials, 2008, 17, 2080-2083.	1.8	13
167	A summary of recent experimental research on ion energy and charge states of pulsed vacuum arcs. , 2008, , .		5
168	High charge state ions extracted from metal plasmas in the transition regime from vacuum spark to high current vacuum arc. , 2008, , .		1
169	Extractable, elevated ion charge states in the transition regime from vacuum sparks to high current vacuum arcs. Applied Physics Letters, 2008, 92, .	1.5	43
170	Studies of III-Nitride Superlattice Structures Implanted with Lanthanide Ions. Materials Research Society Symposia Proceedings, 2008, 1111, 1.	0.1	3
171	Measurements of the asymmetric dynamic sheath around a pulse biased sphere immersed in flowing metal plasma. Plasma Sources Science and Technology, 2008, 17, 035030.	1.3	2
172	Some Applications of Cathodic Arc Coatings. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 429-490.	0.1	1
173	Temporal development of ion beam mean charge state in pulsed vacuum arc ion sources. Review of Scientific Instruments, 2008, 79, 02B301.	0.6	13
174	Inverted end-Hall-type low-energy high-current gaseous ion source. Review of Scientific Instruments, 2008, 79, 02B302.	0.6	3
175	A study of vacuum arc ion velocities using a linear set of probes. Journal Physics D: Applied Physics, 2008, 41, 205210.	1.3	12
176	Observation of Ti4+ ions in a high power impulse magnetron sputtering plasma. Applied Physics Letters, 2008, 93, .	1.5	56
177	Effects of ozone oxidation on interfacial and dielectric properties of thin HfO2 films. Journal of Applied Physics, 2008, 104, 054117.	1.1	14
178	Modification of Surface and Tribological Properties of DLC Films by Adding Silver Content. , 2008, , .		0
179	Cathodic Arc Sources. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 227-263.	0.1	6
180	The Interelectrode Plasma. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 175-225.	0.1	1

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181	A Brief History of Cathodic Arc Coating. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 7-74.	0.1	1
182	Macroparticle Filters. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 299-362.	0.1	1
183	Low-energy linear oxygen plasma source. Review of Scientific Instruments, 2007, 78, 043304.	0.6	10
184	Charge-state-resolved ion energy distribution functions of cathodic vacuum arcs: A study involving the plasma potential and biased plasmas. Journal of Applied Physics, 2007, 101, 043304.	1.1	39
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